

**PROBLEM ONE: (40 points)****NO PARTIAL CREDIT**

A p-n junction is biased at 0.1 V forward bias. The p-side is doped at  $10^{18} \text{ cm}^{-3}$ . The n-side is doped at  $10^{14} \text{ cm}^{-3}$ . Find the following:

A) Electron density on the n-side far from the junction.

$$10^{14} \text{ cm}^{-3}$$

B) Electron density on the n-side at the edge of the depletion region.

$$\text{Almost unchanged } \approx 10^{14} \text{ cm}^{-3}$$

C) Electron density on the p-side far from the junction.

$$n = \frac{n_i^2}{P} = \frac{10^{20}}{10^{18} \text{ cm}^{-3}} = 10^2 \text{ cm}^{-3}$$

D) Electron density on the p-side at the edge of the depletion region.

$$e^{qV/kT} \times \text{part C)} = e^{0.1/0.026} \times 10^2 \text{ cm}^{-3} \approx 5 \times 10^3 \text{ cm}^{-3}$$

E) Hole density on the n-side far from the junction.

$$P = \frac{n_i^2}{n} = \frac{10^{20}}{10^{14}} \text{ cm}^{-3} = 10^6 \text{ cm}^{-3}$$

F) Hole density on the n-side at the edge of the depletion region.

$$e^{qV/kT} \times \text{part E)} \approx 5 \times 10^7 \text{ cm}^{-3}$$

G) Hole density on the p-side far from the junction.

$$10^{18} \text{ cm}^{-3}$$

H) Hole density on the p-side at the edge of the depletion region.

$$\text{Almost unchanged } 10^{18} \text{ cm}^{-3}$$

**PROBLEM TWO(60 points):****(NO PARTIAL CREDIT)**

Consider an MOS capacitors. The metal has a large work function, of 5 eV. (E.G. nickel). The oxide is SiO<sub>2</sub> with a thickness of 20 nm.

- A) The Si is n-doped so that  $E_c - E_f = 0.25 E_g$ . Find the voltage needed to be applied to the gate to achieve flat band condition. Assume  $Q_{ox} = 0$ .

$$V_{FB} = \phi_m - \phi_s = 5 \text{ eV} - \left[ 4.05 \text{ eV} + \frac{1}{4} 1.12 \text{ eV} \right]$$

$$= \boxed{0.67 \text{ V}}$$

- B) Calculate the threshold voltage.

$$V_t = V_{FB} - 2\phi_B - \frac{\sqrt{2\epsilon_{Si} q N_a 2\phi_B}}{C_{ox}}$$

$$= \cancel{+0.67} - 0.56 - 0.054 \text{ V} = \boxed{+0.056 \text{ V}}$$

- C) Let  $Q_{ox} = 10^{10} \text{ cm}^{-2}$ . Find the shift in the threshold voltage.

$$\Delta V_g = \frac{Q_{ox}}{C_{ox}} = \boxed{10 \text{ mV}}$$

$$Q_{ox} = 1.6 \times 10^{21} \text{ C/cm}^2 \text{ (} q \text{ missing)}$$

- D) The Si is p-doped so that  $E_f - E_v = 0.25 E_g$ . Find the voltage needed to be applied to the gate to achieve flat band condition. Assume  $Q_{ox} = 0$ .

$$V_{FB} = \phi_m - \phi_s = 5 \text{ eV} - \left[ 4.05 + \frac{3}{4} 1.12 \right] = \boxed{0.11 \text{ V}}$$

- E) Calculate the threshold voltage.

$$V_t = V_{FB} + 2\phi_B + \frac{\sqrt{2\epsilon_{Si} q N_a 2\phi_B}}{C_{ox}}$$

$$= \underset{0.11}{\cancel{0.67}} + 0.56 + 0.054 \text{ V} = \boxed{0.72 \text{ V}}$$

- F) Let  $Q_{ox} = 10^{10} \text{ cm}^{-2}$ . Find the shift in the threshold voltage.

$$\Delta V_t < \boxed{10 \text{ mV}}$$